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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.	
10/065,277	09/30/2002	Roman Chistyakov	ZON-001	5690	
23701	7590 01/11/2006		EXAM	INER	
RAUSCHENBACH PATENT LAW GROUP, LLC			MCDONALD, RO	MCDONALD, RODNEY GLENN	
P.O. BOX 38 BEDFORD,			ART UNIT	PAPER NUMBER	
			1753		
			DATE MAILED: 01/11/2006	5	

Please find below and/or attached an Office communication concerning this application or proceeding.



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		Application No.	Applicant(s)
Office Action Summary		10/065,277	CHISTYAKOV, ROMAN
		Examiner	Art Unit
		Rodney G. McDonald	1753
Period	The MAILING DATE of this communication app for Reply	pears on the cover sheet with the	correspondence address
WH - Ex aft - If f - Fa An	HORTENED STATUTORY PERIOD FOR REPLY ICHEVER IS LONGER, FROM THE MAILING Doctorisons of time may be available under the provisions of 37 CFR 1.1 er SIX (6) MONTHS from the mailing date of this communication. NO period for reply is specified above, the maximum statutory period villure to reply within the set or extended period for reply will, by statute by reply received by the Office later than three months after the mailing rined patent term adjustment. See 37 CFR 1.704(b).	ATE OF THIS COMMUNICATION 36(a). In no event, however, may a reply be to will apply and will expire SIX (6) MONTHS from the application to become ABANDON	DN. imely filed m the mailing date of this communication. IED (35 U.S.C. § 133).
Status			
2a)∑	Responsive to communication(s) filed on <u>07 N</u> This action is FINAL . 2b) ☐ This Since this application is in condition for alloware closed in accordance with the practice under E	action is non-final.	
Disposi	ition of Claims		
5) <u></u> 6)⊠	Claim(s) <u>1-50</u> is/are pending in the application 4a) Of the above claim(s) is/are withdraw Claim(s) is/are allowed. Claim(s) <u>1-50</u> is/are rejected. Claim(s) is/are objected to. Claim(s) are subject to restriction and/o	wn from consideration.	
Applica	ition Papers		
9)[The specification is objected to by the Examine	r.	
10)[The drawing(s) filed on is/are: a)☐ acc	•	
	Applicant may not request that any objection to the		· ·
11)[Replacement drawing sheet(s) including the correct The oath or declaration is objected to by the Ex		
Priority	under 35 U.S.C. § 119		
а	Acknowledgment is made of a claim for foreign All b Some * c None of: 1. Certified copies of the priority documents 2. Certified copies of the priority documents 3. Copies of the certified copies of the priority documents application from the International Bureau See the attached detailed Office action for a list	s have been received. s have been received in Applica rity documents have been receiv u (PCT Rule 17.2(a)).	tion No ved in this National Stage
Attachme	ent(s)		
i)	ice of References Cited (PTO-892) ice of Draftsperson's Patent Drawing Review (PTO-948) promation Disclosure Statement(s) (PTO-1449 or PTO/SB/08) iter No(s)/Mail Date	4) Interview Summar Paper No(s)/Mail D 5) Notice of Informal 6) Other:	



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DETAILED ACTION

Continued Examination Under 37 CFR 1.114

A request for continued examination under 37 CFR 1.114, including the fee set forth in 37 CFR 1.17(e), was filed in this application after final rejection. Since this application is eligible for continued examination under 37 CFR 1.114, and the fee set forth in 37 CFR 1.17(e) has been timely paid, the finality of the previous Office action has been withdrawn pursuant to 37 CFR 1.114. Applicant's submission filed on October 27, 2005 has been entered.

Claim Rejections - 35 USC § 102

The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

(b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.

Claims 1, 5-10, 13, 14, 16, 19, 20, 22-31, 34, 37, 38 and 40-50 are rejected under 35 U.S.C. 102(b) as being anticipated by Kouznetsov (WO 98/40532).

Kouznetsov teach in Fig. 2 a magnetron sputtering device. The sputtering device has a sputtering chamber 1 and a target 9. The substrate 13 is attached to some electrically isolating support 15 at the end of a wall. (Page 8 lines 29-37; Column 9 lines 1-6) A magnet or magnets 17 are mounted so that the north pole or poles are arranged at the periphery of the target and the south pole or poles at the center of the target 9. One electrode, the anode, is formed by the electrically conducting walls 5 of the housing 3, which e.g. can be grounded. The other



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electrode, *the cathode, is formed by the target 9*, which is thus negatively biased in relation to the anode. The substrate 13 can have some neutral electric potential. A gas inlet for a suitable gas to be ionized such as argon is indicated at 21. (Page 9 lines 7-20) It should be noted that the anode and cathode always have a gap in order to create the plasma. (Applies to Applicant's claim 41)

When increasing the voltage form zero and on between the anode 5 and the cathode 9, there will for some applied voltage appear an electric glow discharge. The gas in the region between the anode and the cathode will be partly ionized by electrons. The electrons will be somewhat trapped or confined by the magnetic field primarily moving in the areas of low magnetic field intensity. (Page 9 lines 21-25) Inherently ground state atoms exist because the gas is not ionized initially. Electrons are needed to ionize in the partially ionized state and the fully ionized state discussed below. (Applies to Applicant's claims 42, 43, 46 and 48)

An electric discharge occurs between the cathode and the anode producing electrons trapped in the magnetic field by cooperation of the electric field produced by the applied voltage. (Page 4 lines 27-31)

When increasing the voltage and current more, there will appear the state comprising *completely ionized plasma region 27*, the region being stationary located above the surface of the target 9 and having a larger extension laterally, in the direction of the surface of the target 9 than the regions 23 of high electron and ion density used in ordinary sputtering. *This state is made possible by the arrangement of the electric and magnetic fields crossing each other in the magnetron* configuration.



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Furthermore, in this state, owing to the considerable extension and the relative homogeneity and uniformity of the ionized plasma in the region 27, *ions will hit the target surface more regularly and uniformly distributed over the surface. This will result in a more homogeneous wear of the target surface*, as illustrated by the area delimited by the dashed line 29 in Fig. 5b. (Page 10 lines 13-23)

The power source is a pulse generator used primarily to produce coatings by sputtering. The power of each pulse can be in the range of 0.1 KW to 1 MW. The pulses can have a duration in the range of less than a hundred microseconds up to hundreds of microseconds and the intervals between pulses can range from milliseconds up to seconds. (Page 4 lines 14-23)

The voltage can be hundreds of volts up to several kilovolts. (Page 6 lines 24-25) The rise time is calculated form the time and voltage discussed above. (Applies to Applicant's claims 44, 45, 49 and 50)

The electric circuit will be generate at the frequency of the main supply typically with *a frequency of 50 or 60 Hz.* (Page 12 lines 14-15)

Alternating current is supplied from the power supply. (Page 6 lines 15-16)

Claims 1, 4, 5, 7, 13, 14, 16, 19-25, 27-29, 32, 33, 37 and 40 are rejected under 35 U.S.C. 102(b) as being anticipated by Mozgrin et al. "High Current Low-Pressure Quasi-Stationary Discharge in a Magnetic Field: Experimental Research", Plasma Physics Reports, Vol. 21, No. 5, 1995, pp. 400-409.

Mozgrin et al. teach a sputtering system as seen in Figure 1 having a cathode (1), an anode (2) and a magnetic system (3). (See Figure 1 pp. 401)



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